

MAGPULS MP 2 - HC BIPOLAR HiPIMS Pulse Power Supply













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World Wide Sales & Support through Dynamic Partners



Highest flexibilty

Supreme performance for Ambitious Reactive Sputtering -Production of Flat Panel Displays, Solar Cells, Decorative / Hard Coatings.

MAGPULS HIPIMS Bi-Polar Pulse Power Supply series MP2-HC are designed for operating with dual magnetrons for reactive sputtering on substrates like glass, plastic & metallic materials. Individual operating modes and enhanced ARC-management allows the MP2-HC to operate effectively in achieving high quality coatings. Typical applications are production of Flat Panel Displays, Solar Cells, Decorative & Hard Coatings.

MP2-HC series consists of mainly two units. The first unit is the DC power supply, which provides the DC power into the big capacitor bank of the pulse unit. The second unit is the Pulsar, an intelligent circuitry, which is equipped with highly sophisticated ARC management capability. MP2-HC series

units are available with an output power range from 10 kW up to 60 kW and pulse current from 400 A up to 1500 A peak current.

MP2-HC Duty Cycle can be adjusted individually for each half-wave to achieve higher target utilisation & for better optimisation of the processes. Enhanced ARC management provides best coating results without process interruptions. Optionally, MP2-HC series provide an external Optical Input Interface for external controlling of the pulse times externally. It also has as an Optical Output Interface for triggering or synchronization of other bipolar pulse power supplies of series MP1-HC or MP2-HC.

VOLTAGE PULSING - Descrete Advantage

MAGPULS MP2-HC Pulse Generators are designed on Voltage Pulsing Technology (VPT). Unlike in Current Pulsing Technology, users can set the amplitude of the Pulse (voltage) in VPT Pulsars. This provides a very tight control on the process. Stable plasma condition is easily achievable at low pulsing frequencies, well below 100kHz. Pulsing current is in correlation with the plasma impedance & temperature stress on the coating products can be controlled very effectively.

Features and Benefits

Adjustable Pulse Parameters & Frequency	Universal Application Range One power supply
6 Different Output operating modes	Optimal adjustment of process for better process stability
DC, Uni-Polar Pulse, Bi-Polar Pulse & Programmable Puls Train	Better control of power optimized target utilization
Enhanced Effective ARC management	Quick Arc-suppression. Lowest Arc-energy. Best results
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Independent +ve and -ve Pulse & Arc Parameters	Highly Effective results for Dual Sputtering processes

MP 2 - HC Series BIPOLAR HIPIMS Pulse Power Supply



	MP2-HC 400	MP2-HC 750	MP2-HC 1000	MP2-HC 1500	
OUT PUT					
Voltage		0 - 1000 V			
Current	0 - 20 A DC 0 - 400 A Pulse	0 - 40 A DC 0 - 750 A Pulse	0 - 60 A DC 0 - 1000 A Pulse	0 - 120 A DC 0 - 1500 A Pulse	
Power	0 - 10 kW DC	0 - 20 kW DC	0 - 30 kW DC	0 - 60 kW DC	
Pulse Frequency	DC DC 0.05 Hz - 50 kHz 0.05 Hz - 30 kHz				
Max. Frequency with Max. Pulse Current	50 kHZ at 100 A 5 kHZ at 400 A	30 kHZ at 120 A 5 kHZ at 750 A	30 kHZ at 150 A 5 kHZ at 1000 A	30 kHZ at 240 A 5 kHZ at 1500 A	
Pulse Time Settings Ton+ / Ton- / Toff+ / Toff-	5.0 μs up to 100 sec				
Duty Cycle		0.005 % to	0 100 %		
Pulse wave form	DC+ Unipolar pulse Programmable Pulse Train				
IN PUT					
Max. Voltage		0 - 1000) V DC		
Max. Current	0 - 20 A DC	0 - 40 A DC	0 - 60 A DC	0 - 120 A DC	
Max. Power	0 - 10 kW DC	0 - 20 kW DC	0 - 30 kW DC	0 - 60 kW DC	
Mains Supply	1 Ф	230 V AC 50/60 Hz or	- 1 Ф 115 V AC 50/60) Hz	
ADC MANIACEMENT					
ARC-MANAGEMENT					
Imax-Detection	0 ± 400 A peak	0 ± 750 A peak	0 ± 1000 A peak	0 ± 1500 A peak	
	0 ± 400 A peak	0 ± 750 A peak		0 ± 1500 A peak	
I _{max} -Detection	0 ± 400 A peak) ns	0 ± 1500 A peak	
Imax-Detection ARC-Detection Time Off Time after ARC-	0 ± 400 A peak	< 200	0 ns 1000 ms	0 ± 1500 A peak	
Imax-Detection ARC-Detection Time Off Time after ARC- Detection		< 200 30 μs up to	0 ns 1000 ms 0 µs		
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time	· · · · · · · · · · · · · · · · · · ·	< 200 30 μs up to ≥ 200	0 ns 1000 ms 0 μs A/μs up to 2000 A/μs		
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change	Va	< 200 30 µs up to ≥ 200 ′ar. di/dt threshold: 0 /	0 ns 1000 ms 0 μs A/μs up to 2000 A/μs to 100 % Upc (Optio	n)	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU	Va	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 % r. U threshold: 0 % up Var. U threshold: 0	0 ns 1000 ms 0 μs A/μs up to 2000 A/μs to 100 % Upc (Optio	n)	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection	Var. I thre	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 % r. U threshold: 0 % up Var. U threshold: 0	0 ns 0 1000 ms 0 μs A/μs up to 2000 A/μs to 100 % Upc (Option) 0 V up to 1000 V k up to 1 x max Ipeak (n) Option)	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 / r. U threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. I _{pea}	Ons 1000 ms O µs A/µs up to 2000 A/µs to 100 % Ubc (Option O V up to 1000 V k up to 1 x max Ipeak (n) Option) wer supplies	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection INTERFACE Analog	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 % r. U threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. Ipea	Ons 1000 ms O μs A/μs up to 2000 A/μs to 100 % Upc (Option O V up to 1000 V k up to 1 x max Ipeak (Illing external DC point floating potential co	n) Option) wer supplies	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection INTERFACE Analog Digital	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 2ar. di/dt threshold: 0 % up Var. U threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. Ipea pin-Sub-D for controp-D user Interface with	Ons 1000 ms O μs A/μs up to 2000 A/μs to 100 % Upc (Option O V up to 1000 V k up to 1 x max Ipeak (Illing external DC point floating potential coub-D	n) Option) wer supplies	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection INTERFACE Analog Digital RS 232	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 2ar. di/dt threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. Ipea pin-Sub-D for contro p-D user Interface with 9 pin S	Ons 1000 ms A/μs up to 2000 A/μs to 100 % Upc (Option OV up to 1000 V k up to 1 x max Ipeak (Illing external DC point floating potential coub-D	n) Option) wer supplies	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection INTERFACE Analog Digital RS 232 Ethernet	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. Ipea o pin-Sub-D for contropodo D user Interface with 9 pin S RJ 4	Ons 1000 ms A/μs up to 2000 A/μs to 100 % Upc (Option OV up to 1000 V k up to 1 x max Ipeak (Illing external DC point floating potential coub-D	n) Option) wer supplies	
Imax-Detection ARC-Detection Time Off Time after ARC-Detection ARC-Recovery Time di/dt Dynamic Change Voltage Drop ΔU U x I - Cross Detection INTERFACE Analog Digital RS 232 Ethernet Profibus	Var. I thro 1 (up to 3) 15	< 200 30 µs up to ≥ 200 'ar. di/dt threshold: 0 % up Var. U threshold: 0 % up Var. U threshold: 0 eshold: 0.1 x max. Ipea pin-Sub-D for controp-D user Interface with 9 pin S RJ 4 9 pin Sub-D	Ons 1000 ms A/μs up to 2000 A/μs to 100 % Upc (Option OV up to 1000 V k up to 1 x max Ipeak (Illing external DC point floating potential coub-D	option) Wer supplies ontactors	

MP 2 - HC Series BIPOLAR HiPIMS Pulse Power Supply



	MP2-HC 400	MP2-HC 750	MP2-HC 1000	MP2-HC 1500
ENV CONDITION				
Ambient Temperature	+ 5 °C up to + 35 °C			
Max. Humidity	80 % non condensing			
Max. Operation Altitude	1500 m above sea level			
MECHANICAL DATA				
Construction	19"-Rack 5 HU		19"-Rack 12 HU	
Dimensions H x W x D	266.7.25 mm x 483 mm x 650 mm		533.4 mm x 483 mm x 700 mm	
Weight	36 kg	42 kg	80 kg	85 kg
DISPLAY & CONTROLS				
Display	Graphic color display			
LED Display	Power, OK, Start / Stop			
Controls	Graphical menu via function keys, arrow keys and continous rotating knob			
SUITABILITY				
Application	Hard Coating on Tools & Bits and BIAS application			
Process	PVD, Plasma Nitriding, Pulse Plasma, Reactive Sputtering, Dual & Single Magnetron Sputtering			
Material	Metals			

Please contact us for information on higher capacity models & other variants

BP Symmetric & BP Asymmetric

MP2-HC HIPIMS Pulse Generators are available in 2 variants: Bi-Polar Symmetric (MP2-HC-S) & Bi-Polar Asymmetric (MP2-HC-AS). In Symmetric variant, +ve and -ve Pulses will have the same Pulse Voltage settings, whereas in Asymmetric variant, users can set different values for Pulse Voltage outputs. This gives the user higher control and advantage in the Dual Magnetron Sputtering processes



OUT PUT Waveforms











